

WHAT IS CLAIMED IS:

1. A manufacturing apparatus comprising:
 - a loading chamber;
 - 5 a transporting chamber coupled to the loading chamber;
 - a plurality of film formation chambers coupled to the transporting chamber;
 - a processing chamber coupled to the transporting chamber;
 - wherein each of the plurality of film formation chambers is coupled to a vacuum evacuation processing chamber for making the inside of the film formation
 - 10 chamber vacuum;
 - wherein each of the plurality of film formation chambers comprises:
 - an alignment means for performing a position alignment of a mask and a substrate;
 - a substrate holding means;
 - 15 an evaporation source holder; and
 - a means for moving the evaporation source holder;
 - wherein the evaporation source holder comprises:
 - a container that seals an evaporation material;
 - a means for heating the container; and
 - 20 a shutter formed over the container;
 - wherein the processing chamber is coupled to a vacuum evacuation processing chamber for providing a vacuum state,
 - wherein a plurality of plate heaters are disposed within the processing chamber so as to overlap and open gaps therebetween, and
 - 25 wherein the processing chamber can perform vacuum heating on a plurality of substrates.

2. A manufacturing apparatus according to claim 1, wherein a means for moving the evaporation source holder functions to move the evaporation source

holder in an x-axis direction at a certain pitch, and functions to move the evaporation source holder in a y-axis direction at a certain pitch.

3. A manufacturing apparatus according to claim 1, wherein the evaporation
5 source holder is rotated when switching between the x-axis direction and the y-axis direction.

4. A manufacturing apparatus according to claim 1, wherein a hole of an
opening surface area S2, which is smaller than an opening surface area S1 of the
10 container, is opened in the shutter.

5. A manufacturing apparatus according to claim 1, wherein a film
thickness monitor is formed adjacent to the evaporation source holder.

15 6. A manufacturing apparatus according to claim 1, wherein the inert gas
element comprises at least one selected from the group consisting of He, Ne, Ar, Kr,
and Xe.

7. A manufacturing apparatus comprising:
20 a loading chamber;
a transporting chamber coupled to the loading chamber;
a plurality of film formation chambers coupled to the transporting chamber;
a processing chamber coupled to the transporting chamber;
wherein each of the plurality of film formation chambers is coupled to a
25 vacuum evacuation processing chamber for making the inside of the film formation
chamber vacuum;
wherein each of the plurality of film formation chambers comprises:
an alignment means for performing position alignment of a mask
and a substrate;

a substrate holding means;
an evaporation source holder; and
a means for moving the evaporation source holder;
wherein the evaporation source holder comprises:
5 a container that seals an evaporation material;
a means for heating the container; and
a shutter formed over the container;
wherein the processing chamber is coupled to a vacuum evacuation
processing chamber for providing a vacuum state, and
10 wherein at least one of a hydrogen gas, an oxygen gas, and an inert gas is
introduced in the processing chamber to generate a plasma.

8. A manufacturing apparatus according to claim 7, wherein a plurality of
plate heaters are disposed in the transporting chamber so as to overlap and open
15 gaps therebetween and a processing chamber capable of performing vacuum heating
on a plurality of substrates is coupled to the transporting chamber.

9. A manufacturing apparatus according to claim 7, wherein a means for
moving the evaporation source holder functions to move the evaporation source
20 holder in an x-axis direction at a certain pitch, and functions to move the
evaporation source holder in a y-axis direction at a certain pitch.

10. A manufacturing apparatus according to claim 7, wherein the
evaporation source holder is rotated when switching between the x-axis direction
25 and the y-axis direction.

11. A manufacturing apparatus according to claim 7, wherein a hole of an
opening surface area S2, which is smaller than an opening surface area S1 of the
container, is opened in the shutter.

12. A manufacturing apparatus according to claim 7, wherein a film thickness monitor is formed adjacent to the evaporation source holder.

5 13. A manufacturing apparatus according to claim 7, wherein the inert gas element comprises at least one selected from the group consisting of He, Ne, Ar, Kr, and Xe.